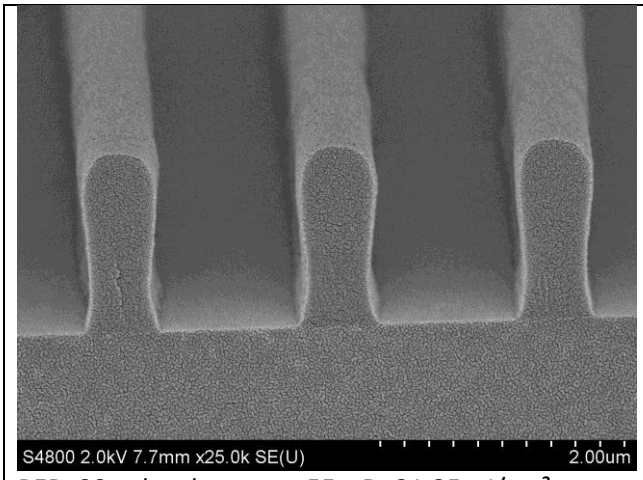
AZ5214 (image reversal)

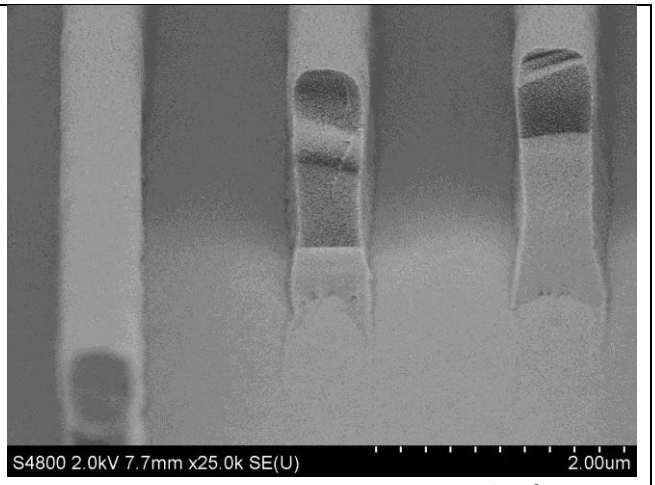
Tone	Negative
Reference	http://www.microchemicals.com/products/photoresists/az_5214e.html
Spincoat	primer HMDS: 3000rpm, bake on hotplate 200°C for 2 minutes
	AZ5214: 4000rpm gives a 1.4µm thick layer, 5000rpm 1.25µm
Bake	in oven at 90°C for 15 minutes
Exposure	15 to 25 mJ/cm²
Post-exposure bake (PEB)	in oven at 120°C for 32 to 52s
Flood exposure	EVG 15s
Development	MF321 for 50 to 90s
Rinse	water

Depending on the desired profile (etchmask or undercut profile for lift-off) parameters like post-exposure time, development time and dose should be selected.

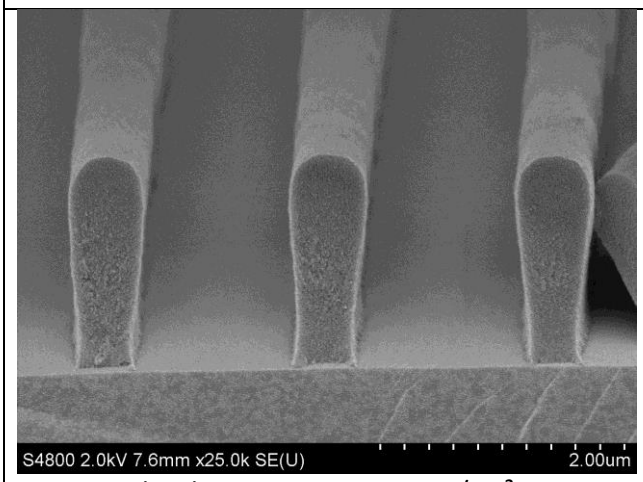
0.6µm structures:



PEB=32s, development=55s, D=21.25mJ/cm²

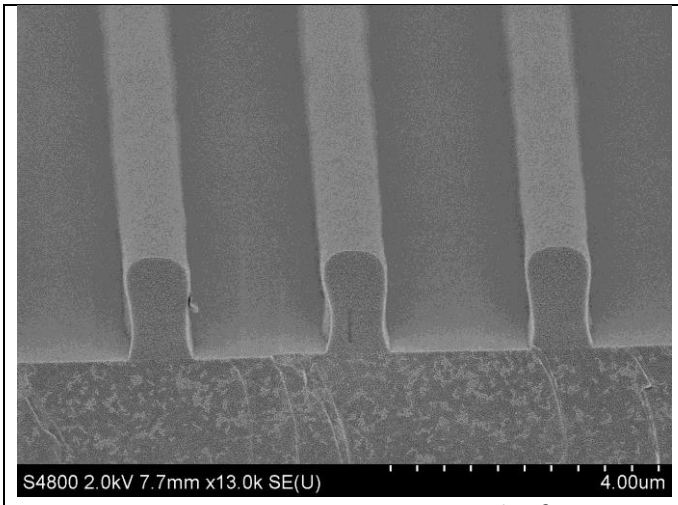


PEB=52s, development=55s, D=16.25mJ/cm²

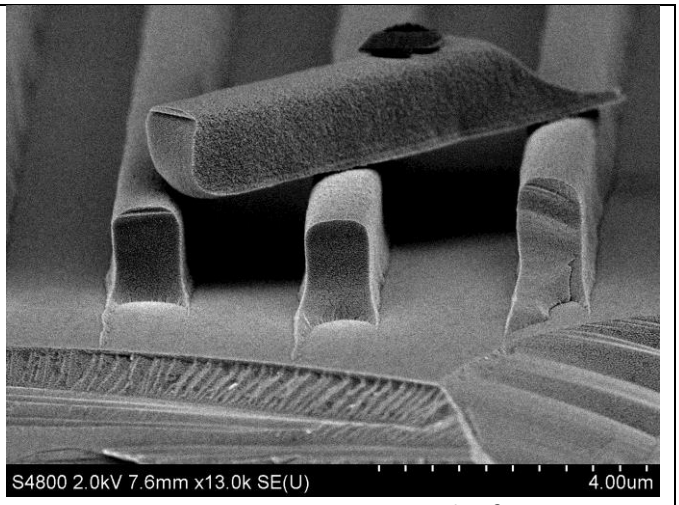


PEB=32s, development=90s, D=25mJ/cm²

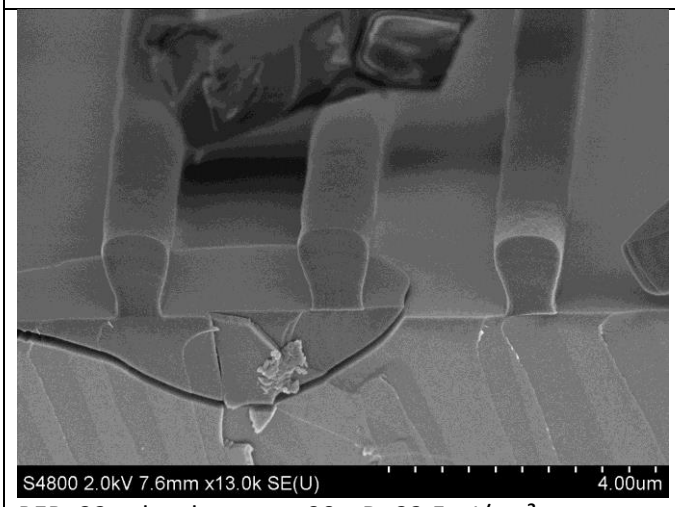
1µm structures:



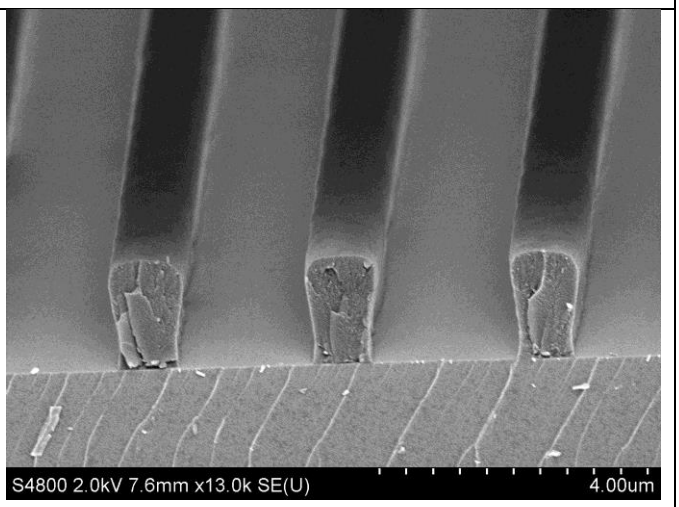
PEB=32s, development=55s, D=18.75mJ/cm²



PEB=52s, development=55s, D=15mJ/cm²

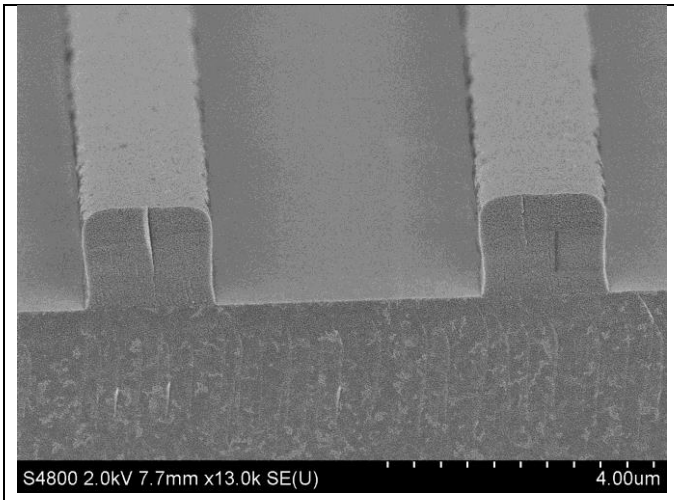


PEB=32s, development=90s, D=22.5mJ/cm²

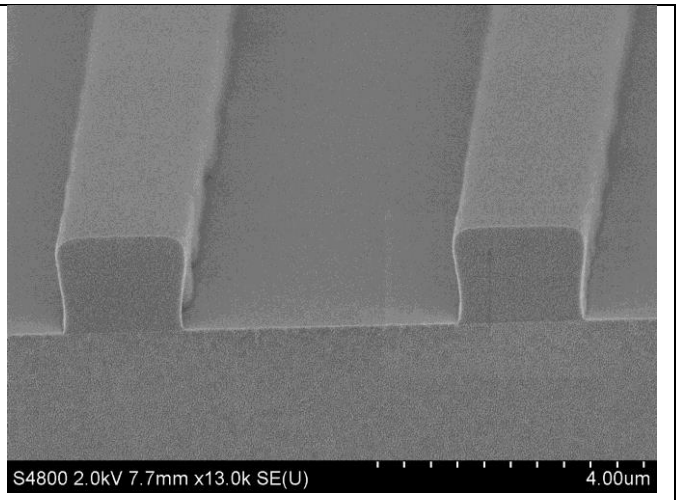


PEB=52s, development=90s, D=20mJ/cm²

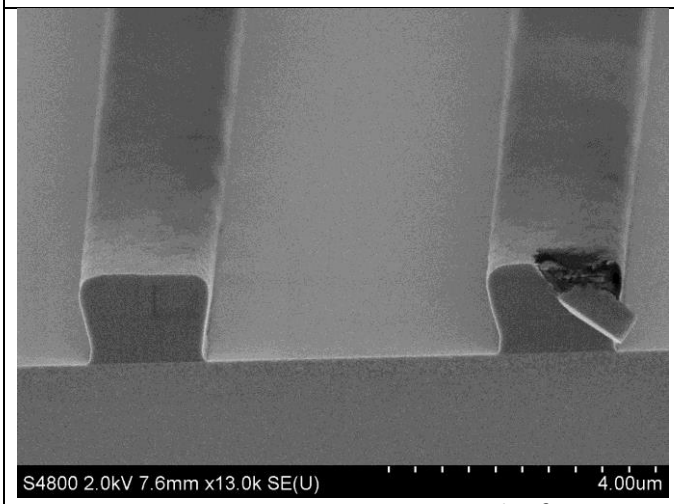
2µm structures:



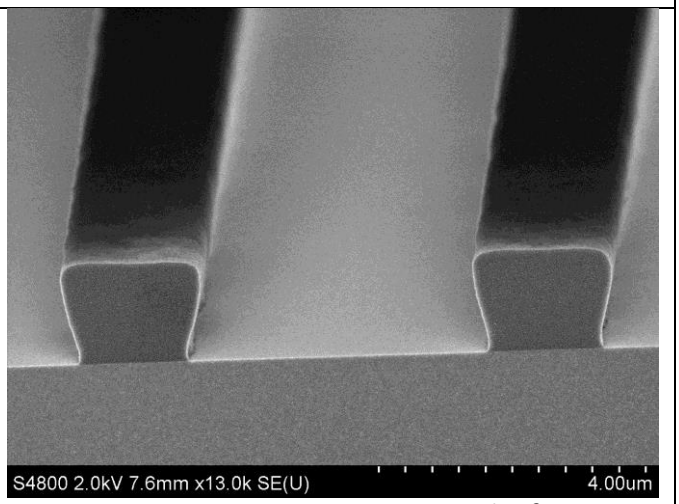
PEB=32s, development=55s, D=18.75mJ/cm²



PEB=52s, development=55s, D=15mJ/cm²



PEB=32s, development=90s, D=21.25mJ/cm²



PEB=52s, development=90s, D=18.75mJ/cm²

5µm structures:

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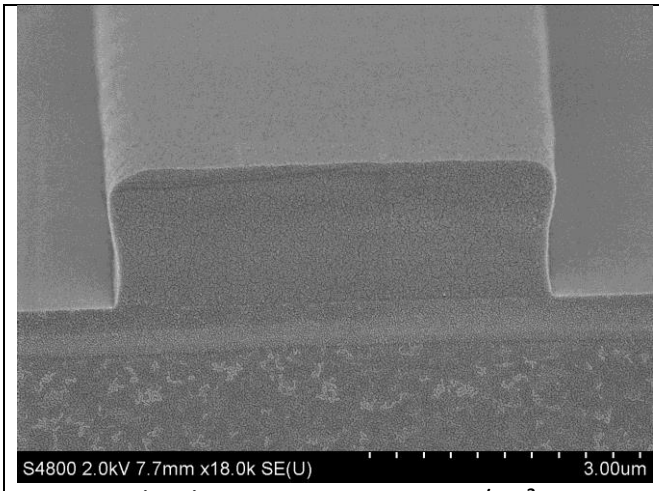
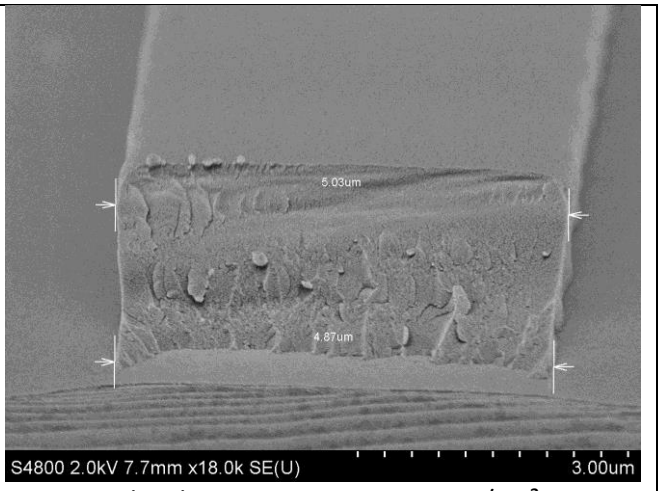
<td> 

PEB=32s, development=55s, D=17.5mJ/cm²</td>
<td> 

PEB=52s, development=55s, D=13.75mJ/cm²</td>
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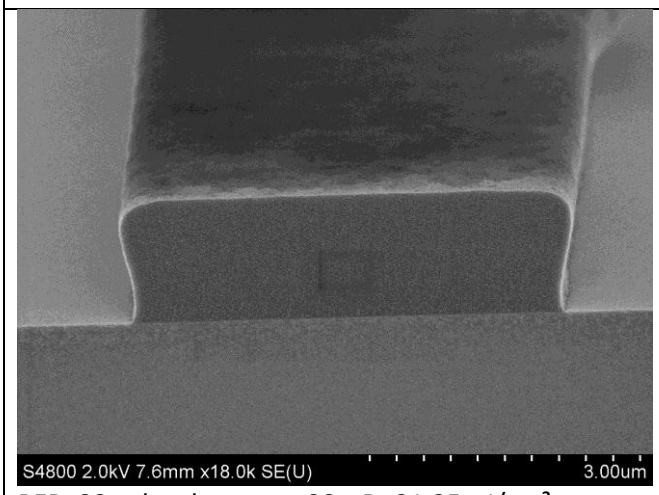
<td> 

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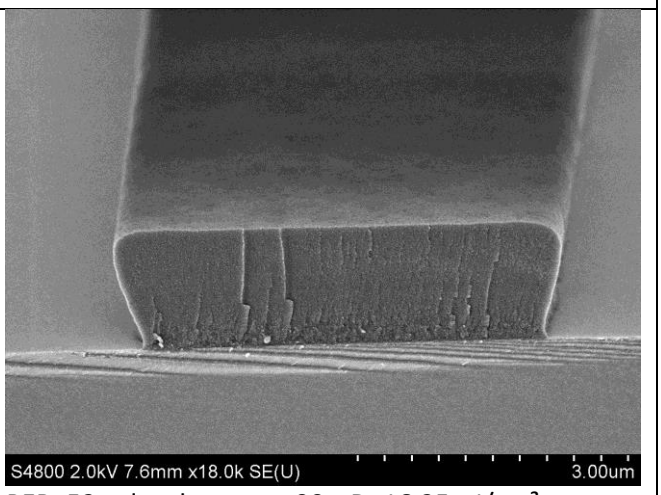
<td> 

PEB=52s, development=90s, D=16.25mJ/cm²</td>
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